

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	276	RICHARDSON-JOHN	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:08
S2	36	RICHARDSON-JOHN-G	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:08
S3	2	RICHARDSON-JOHN-GILBERT	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:08
S4	21	S2 and conductiv\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:10
S5	1	S2 and conductiv\$5 and lump\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:09
S6	31	S1 and conductiv\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:10
S7	9	S1 and conductiv\$5 and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:12
S8	0	S1 and conductiv\$5 and (resistance\$1 or resistivit\$4) and lump\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:10
S9	806	bechtel.asn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:12

S10	30	S9 and conductiv\$5 and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:12
S11	0	S9 and conductiv\$5 and (resistance\$1 or resistivit\$4) and lump\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 09:12
S12	0	("6889557").URPN.	USPAT	OR	OFF	2005/06/14 09:19
S13	38	("20030161946" "3596269" "3740522" "3742350" "4092950" "4340010" "4420251" "4472621" "4514443" "4529974" "4661682" "4677371" "4704985" "4736157" "4774905" "4853515" "4926165" "5015958" "5024423" "5181962" "5185183" "5195046" "5279148" "5369366" "5410255" "5412173" "5416280" "5551484" "5573814" "5602492" "5743299" "5951761" "6058978" "6085413" "6194890" "6197168" "6320400" "6501278").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:21
S14	1801	(lump\$3 with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:22
S15	588	(lump\$3 with (resistance\$1 or resistivit\$4)) and conductive	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:23
S16	198	(lump\$3 with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 10:45
S17	35	"4814690"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:30
S18	2	S17 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:31
S19	8	"5165794"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:31

S20	1	S19 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:32
S21	10	"5381333"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:32
S22	5	S21 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:34
S23	12	"5911158"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:34
S24	1	S23 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:35
S25	2	"6088655"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:35
S26	2	S25 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:37
S27	2	"6501984"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:37
S28	2	S27 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:38
S29	1	"20030196485"	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:38
S30	0	S29 and conductive and (resistance\$1 or resistivit\$4)	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 09:38
S31	1141	((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 10:55
S32	14	((lump\$3 or net) with (resistance\$1 or resistivit\$4) with (model\$1 or modelling\$1)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; USOCR	OR	OFF	2005/06/14 10:46
S33	712	((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 13:54

S34	12	((lump\$3 or net) with (resistance\$1 or resistivit\$4) with (model\$1 or modelling\$1)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:43
S35	329	(702/65).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S36	556	(702/57).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S37	305	(702/58).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S38	619	(702/108).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S39	312	(702/127).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S40	66	(702/133).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:05
S41	3	S35 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:06
S42	2	S36 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:07
S43	1	S37 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:44

S44	0	S38 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:06
S45	0	S39 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:06
S46	353	(324/525).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:43
S47	157	(324/649).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:46
S48	364	(324/691).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:44
S49	392	(324/693).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:44
S50	344	(324/696).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:44
S51	1	S46 and ((lump\$3 or net) with (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:46
S52	3	S47 and lump\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:46
S53	8	S47 and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:49

S54	78	S48 and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:50
S55	115	S49 and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 12:14
S56	77	S50 and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 11:59
S57	379	((lump\$3 or net) near3 (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 13:58
S58	178	((lump\$3 or net) near3 (resistance\$1 or resistivit\$4)) and conductive and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4)) and resistivit\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 13:58
S59	52	((lump\$3 or net) near3 (resistance\$1 or resistivit\$4)) and (conductive with film\$1) and ((measur\$8 or detect\$6 or sense\$1 or sensing) with (resistance\$1 or resistivit\$4)) and resistivit\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/14 13:58

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6172407 99
6408754 99
6475713 99
5386195 83
4505847 82
5764595 82
3794912 82
4313101 82
4393176 82
4446357 82
4566992 82
4595790 82
4774023 82
4849050 82
5937317 82
5968847 82
5989999 82
6011090 82
6140223 82
6284832 82
6300049 82
6346353 82
6352805 82
6355406 82
6395149 82
6395459 82
6417265 82
6432509 82
6436619 82
6468223 82
6475695 82
4632777 82
6157081 82
5602423 81
5736457 81
5977519 81
6084280 81
6200865 81
4450429 81
4492111 81
4573065 81
4593339 81
4794226 81
4904613 81
4960965 81
4964947 81
5015858 81
5181968 81
5196373 81
5200733 81

10828633_CLS.txt
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10828633 on June 14, 2005

Original Classifications

3 252/511
2 136/256
2 257/752
2 430/14
2 430/529

Cross-Reference Classifications

5 430/531
4 430/536
3 257/E21.584
3 347/105
3 430/527
2 219/553
2 252/500
2 252/502
2 252/510
2 252/519.32
2 257/413
2 257/E21.165
2 257/E21.583
2 428/480
2 430/201
2 430/207
2 430/512
2 430/533
2 430/961
2 438/648
2 524/524

Combined Classifications

5 430/531
4 252/511
4 430/536
3 257/E21.584
3 347/105
3 430/527
2 136/256
2 219/553
2 252/500
2 252/502
2 252/510
2 252/519.32
2 257/410
2 257/412
2 257/413
2 257/752
2 257/E21.165
2 257/E21.583
2 428/480
2 430/14
2 430/201
2 430/207
2 430/512
2 430/529
2 430/533
2 430/961
2 438/627
2 438/648

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2 524/495
2 524/524

Titles of Most Frequently Occurring Classifications of Patents Returned
From A Search of 10828633 on June 14, 2005

- 5 430/531 (0 OR, 5 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing
- 4 252/511 (3 OR, 1 XR)
Class 252 : COMPOSITIONS
252/500 ELECTRICALLY CONDUCTIVE OR EMISSIVE
COMPOSITIONS
252/502 .Elemental carbon containing
252/510 ..With organic component
252/511 ...Resin, rubber, or derivative thereof
containing
- 4 430/536 (0 OR, 4 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/531 ..Synthetic resin or cellulose derivative
containing
430/536 ...Polymer of unsaturated monomer
- 3 257/E21.584 (0 OR, 3 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/E21.531 ...For electrical parameters, e.g.,
resistance, deep-levels, CV, diffusions by
electrical means
(EPO)
257/E21.532 .Manufacture or treatment of devices
consisting of plurality of solid-state components
formed in
or on common substrate or of parts thereof;
manufacture of
integrated circuit devices or of parts thereof (EPO)
257/E21.536 ..Manufacture of specific parts of devices
(EPO)
257/E21.575 ...Interconnections, comprising conductors and
dielectrics, for carrying current between separate
components within device (EPO)
257/E21.576Characterized by formation and post
treatment of dielectrics, e.g., planarizing (EPO).
257/E21.584Barrier, adhesion or liner layer (EPO)
- 3 347/105 (0 OR, 3 XR)
Class 347 : INCREMENTAL PRINTING OF SYMBOLIC INFORMATION
347/1 INK JET
347/101 .Medium and processing means
347/105 ..Receiving medium
- 3 430/527 (0 OR, 3 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

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430/495.1 RADIATION SENSITIVE PRODUCT
430/523 .Identified backing or protective layer
containing
430/527 ..Antistatic agent containing

2 136/256 (2 OR, 0 XR)
Class 136 : BATTERIES: THERMOELECTRIC AND PHOTOELECTRIC

136/243 PHOTOELECTRIC
136/252 .Cells
136/256 ..Contact, coating, or surface geometry

2 219/553 (0 OR, 2 XR)
Class 219 : ELECTRIC HEATING
219/260 .Resistive element: igniter type
219/538 .With heating unit structure
219/552 ..Heating element structure
219/553 ...Of particular construction and/or material
(e.g., infrared generator)

2 252/500 (0 OR, 2 XR)
Class 252 : COMPOSITIONS
252/500 ELECTRICALLY CONDUCTIVE OR EMISSIVE
COMPOSITIONS

2 252/502 (0 OR, 2 XR)
Class 252 : COMPOSITIONS
252/500 ELECTRICALLY CONDUCTIVE OR EMISSIVE
COMPOSITIONS
252/502 .Elemental carbon containing

2 252/510 (0 OR, 2 XR)
Class 252 : COMPOSITIONS
252/500 ELECTRICALLY CONDUCTIVE OR EMISSIVE
COMPOSITIONS
252/502 .Elemental carbon containing
252/510 ..With organic component

2 252/519.32 (0 OR, 2 XR)
Class 252 : COMPOSITIONS
252/500 ELECTRICALLY CONDUCTIVE OR EMISSIVE
COMPOSITIONS
252/518.1 .Metal compound containing
252/519.3 ..With organic compound
252/519.32 ...The organic compound is a natural resin,
protein, lignin, carbohydrate, or derivative thereof

2 257/410 (1 OR, 1 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/264 ...Enhancement mode or with high resistivity
channel (e.g., doping of 10^{15} cm⁻³ or less)
257/288 .Having insulated electrode (e.g., MOSFET, MOS
diode)
257/410 ..Gate insulator includes material (including
air or vacuum) other than SiO₂

2 257/412 (1 OR, 1 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/264 ...Enhancement mode or with high resistivity
channel (e.g., doping of 10^{15} cm⁻³ or less)
257/288 .Having insulated electrode (e.g., MOSFET, MOS
diode)
257/412 ..Gate electrode of refractory material (e.g.,

group polysilicon or a silicide of a refractory or platinum metal)

2 257/413 (0 OR, 2 XR)
 Class 257 : ACTIVE SOLID-STATE DEVICES
 257/264 ...Enhancement mode or with high resistivity channel (e.g., doping of 10^{15} cm⁻³ or less)
 257/288 .Having insulated electrode (e.g., MOSFET, MOS diode)
 257/412 ..Gate electrode of refractory material (e.g., polysilicon or a silicide of a refractory or platinum metal)

group 257/413 ...Polysilicon laminated with silicide

2 257/752 (2 OR, 0 XR)
 Class 257 : ACTIVE SOLID-STATE DEVICES
 257/734 COMBINED WITH ELECTRICAL CONTACT OR LEAD
 257/741 .Of specified material other than unalloyed aluminum
 257/750 ..Layered
 257/752 ...Planarized to top of insulating layer

2 257/E21.165 (0 OR, 2 XR)
 Class 257 : ACTIVE SOLID-STATE DEVICES
 257/E21.001 PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE OR TREATMENT OF SEMICONDUCTOR OR SOLID-STATE DEVICES OR OF PARTS THEREOF (EPO)

257/E21.002 .Manufacture or treatment of semiconductor device (EPO)

257/E21.04 ..Device having at least one potential-jump barrier or surface barrier, e.g., PN junction, depletion layer, carrier concentration layer (EPO)

257/E21.085 ...Device having semiconductor body comprising Group IV elements or Group III-V compounds with or without impurities, e.g., doping materials (EPO)

257/E21.158Manufacture of electrode on semiconductor body using process other than by epitaxial growth, diffusion of impurities, alloying of impurity materials, or radiation bombardment (EPO)

257/E21.159Deposition of conductive or insulating material for electrode conducting electric current (EPO)

257/E21.16From a gas or vapor, e.g., condensation (EPO)

257/E21.161Of conductive layer (EPO)

257/E21.162On semiconductor body comprising Group IV element (EPO)

257/E21.165Conductive layer comprising silicide (EPO)

2 257/E21.583 (0 OR, 2 XR)
 Class 257 : ACTIVE SOLID-STATE DEVICES
 257/E21.531 ...For electrical parameters, e.g., resistance, deep-levels, CV, diffusions by electrical means (EPO)

257/E21.532 .Manufacture or treatment of devices

consisting of plurality of solid-state components

formed in

or on common substrate or of parts thereof;

manufacture of

integrated circuit devices or of parts thereof (EPO)

257/E21.536 ..Manufacture of specific parts of devices (EPO)

257/E21.575 ...Interconnections, comprising conductors and dielectrics, for carrying current between separate components within device (EPO)

257/E21.576Characterized by formation and post treatment of dielectrics, e.g., planarizing (EPO)

257/E21.583Planarization; smoothing (EPO)

2 428/480 (0 OR, 2 XR)

Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES

428/411.1 COMPOSITE (NONSTRUCTURAL LAMINATE)

428/480 .Of polyester (e.g., alkyd, etc.)

2 430/14 (2 OR, 0 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/9 IMAGED PRODUCT

430/14 .Multilayer

2 430/201 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/199 TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING AN IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN

IMAGE

RECEIVING LAYER

430/200 .Imagewise heating, element or image receiving layers therefor or imagewise vapor and gas transfer process, element or image receiving layer therefor

430/201 ..Imagewise vapor or gas transfer process, element or image receiving layer therefor

2 430/207 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/199 TRANSFER PROCEDURE BETWEEN IMAGE AND IMAGE LAYER, IMAGE RECEIVING LAYERS, OR ELEMENT CONTAINING AN IMAGE RECEIVING LAYER OR AN INGREDIENT FOR FORMING AN

IMAGE

RECEIVING LAYER

430/202 .Diffusion transfer process, element, or identified image receiving layers therefor

430/207 ..Element structurally defined other than containing nominal processing composition container or trap, or containing processing composition container or trap made of identified material

2 430/512 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT

430/510 .Antihalation or filter layer containing

430/512 ..Filters ultraviolet radiation

2 430/529 (2 OR, 0 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,

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COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT

430/523 .Identified backing or protective layer
containing

430/527 ..Antistatic agent containing

430/529 ...Organic carboxylic, sulfur or phosphorus
acid or salt

2 430/533 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/495.1 RADIATION SENSITIVE PRODUCT

430/523 .Identified backing or protective layer
containing

430/531 ..Synthetic resin or cellulose derivative
containing

430/533 ...Polyester or polycarbonate

2 430/961 (0 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/961 PROTECTIVE OR ANTIABRASION LAYER

2 438/627 (1 OR, 1 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/584 COATING WITH ELECTRICALLY OR THERMALLY
CONDUCTIVE MATERIAL

438/597 .To form ohmic contact to semiconductive
material

438/618 ..Contacting multiple semiconductive regions
(i.e., interconnects)

438/622 ...Multiple metal levels, separated by
insulating layer (i.e., multiple level metallization)

438/625At least one metallization level formed of
diverse conductive layers

438/627At least one layer forms a diffusion
barrier

2 438/648 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/584 COATING WITH ELECTRICALLY OR THERMALLY
CONDUCTIVE MATERIAL

438/597 .To form ohmic contact to semiconductive
material

438/618 ..Contacting multiple semiconductive regions
(i.e., interconnects)

438/642 ...Diverse conductors

438/648Having refractory group metal (i.e.,
titanium (Ti), zirconium (Zr), hafnium (Hf), vanadium
(V),
niobium (Nb), tantalum (Ta), chromium (Cr), molybdenum
(Mo), tungsten (W), or alloy thereof)

2 524/495 (1 OR, 1 XR)

Class 524 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES

524/1 ..Adding a NRM to a preformed solid polymer or
preformed specified intermediate condensation product,
composition thereof; or process of treating or
composition thereof

524/495 ...Mixing with carbon, e.g., graphite, etc.,
 having numerical limitations, other than amount, e.g.,
 included herein are particle size, surface area, etc., or
 composition or product thereof, DNRM

2 524/524 (0 OR, 2 XR)
 Class 524 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
 OF THE CLASS 520 SERIES

524/1 ..Adding a NRM to a preformed solid polymer or
 preformed specified intermediate condensation
 product,
 composition thereof; or process of treating or
 composition thereof

524/500 ...Containing two or more solid polymers; solid
 reactant polymer or SICP and a SICP, SPFI, or an ethylenic
 or product thereof

524/502At least one solid polymer derived from
 ethylenic reactants only

524/515Two or more solid polymers derived from
 ethylenic reactants only

524/523Solid polymer derived from carboxylic
 acid ester monomer

524/524Ester derived from an unsaturated
 alcohol and a saturated acid, e.g., vinyl acetate, etc.

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